



**EL 465779878**  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

# 13/P  
9/5/01  
Harrison

Application Serial No. .... 09/212,726  
Filing Date ..... December 15, 1998  
Inventor ..... Klaus Florian Schuegraf  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2813  
Examiner ..... E. Kielin  
Attorney's Docket No. .... MI22-1098  
Title: Semiconductor Processing Methods of Chemical Vapor Depositing  
SiO2 on a Substrate

**RESPONSE TO FEBRUARY 28, 2001 OFFICE ACTION**

To: Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Bernard Berman (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
601 W. First Avenue, Suite 1300  
Spokane, WA 99201-3828

Sir:

Responsive to the Office Action dated February 28, 2001, Applicant respectfully requests reconsideration of the above-referenced application in view of the remarks that follow.

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